

IAP20 Rec'd PGT/PTO 12 JAN 2006

INFORMATION DISCLOSURE STATEMENT

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|-----------|---|---|
| Applicant | : | Masuda et al. |
| App. No | : | Unknown |
| Filed | : | Herewith |
| For | : | POSITIVE PHOTORESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN |
| Examiner | : | Unknown |
| Art Unit | : | Unknown |

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Enclosed for filing in the above-identified application is a PTO/SB/08 Equivalent listing 15 references to be considered by the Examiner. Also enclosed are 10 foreign patent references and/or non-patent literature as listed on the Information Disclosure Statement. Please note that JP 3-191351 corresponds to U.S. 5,290,657; JP 5-232697 corresponds to U.S. 5,424,167; JP 10-97066 corresponds to U.S. 6,210,855; and JP 11-204399 corresponds to U.S. 6,319,853.

This Information Disclosure Statement is being filed within three months of the filing date, and no fee is required.

The Commissioner is hereby authorized to charge any additional fees which may be required, or credit any overpayment, to Account No. 11-1410.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: 12 Jan. 2006

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|--|----------------------|---------------------------|
| INFORMATION DISCLOSURE STATEMENT BY APPLICANT | Application No. | Unknown |
| | Filing Date | Herewith 10/564510 |
| | First Named Inventor | Masuda, Yasuo |
| | Art Unit | Unknown |
| (Multiple sheets used when necessary) | Examiner | Unknown |
| SHEET 1 OF 1 | Attorney Docket No. | SHIGA7.036APC |

| U.S. PATENT DOCUMENTS | | | | | |
|-----------------------|----------|---|--------------------------------|-------------------------------|--|
| Examiner Initials | Cite No. | Document Number Number - Kind Code (if known) Example: 1,234,567 B1 | Publication Date MM-DD-YYYY | Name of Patentee or Applicant | Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear |
| | 1 | 5,290,657 | 03-01-1994 | Uetani et al. | |
| | 2 | 5,424,167 | 06-13-1995 | Uetani et al. | |
| | 3 | 6,210,855 B1 | 04-03-2001 | Ueda et al. | |
| | 4 | 6,319,853 B1 | 11-20-2001 | Ishibashi et al. | |
| | 5 | 6,187,500 B1 | 02-13-2001 | Miyagi et al. | |

| FOREIGN PATENT DOCUMENTS | | | | | | |
|--------------------------|----------|--|--------------------------------|-------------------------------|--|----------------|
| Examiner Initials | Cite No. | Foreign Patent Document Country Code-Number-Kind Code Example: JP 1234567 A1 | Publication Date MM-DD-YYYY | Name of Patentee or Applicant | Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear | T ¹ |
| | 6 | JP 3-191351 | 08-21-1991 | | | |
| | 7 | JP 5-232697 | 09-10-1993 | | | |
| | 8 | JP 2001-312052 | 11-09-2001 | Tokyo Ohka Kogyo Co. | | Abstract |
| | 9 | JP 2001-312059 | 11-09-2001 | Tokyo Ohka Kogyo Co. | | Abstract |
| | 10 | JP 2001-312060 | 11-09-2001 | Tokyo Ohka Kogyo Co. | | Abstract |
| | 11 | JP 2001-312066 | 11-09-2001 | Tokyo Ohka Kogyo Co. | | Abstract |
| | 12 | JP 10-97066 | 04-14-1998 | | | |
| | 13 | JP 11-204399 | 07-30-1999 | | | |
| | 14 | EP 0 677 789 A1 | 10-18-1995 | Fuji Photo Film Co., Ltd. | | |
| | 15 | EP 0 650 091 A1 | 04-26-1995 | Sumitomo Chem. Co. | | |

| NON PATENT LITERATURE DOCUMENTS | | | |
|---------------------------------|----------|---|----------------|
| Examiner Initials | Cite No. | Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published. | T ¹ |
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|--------------------|-----------------|
| Examiner Signature | Date Considered |
|--------------------|-----------------|

*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

T¹ - Place a check mark in this area when an English language Translation is attached.